

**Supporting information for**  
**A facile organosilane-based strategy for direct synthesis of thin**  
**MWW-type titanosilicate with high catalytic oxidation**  
**performance**

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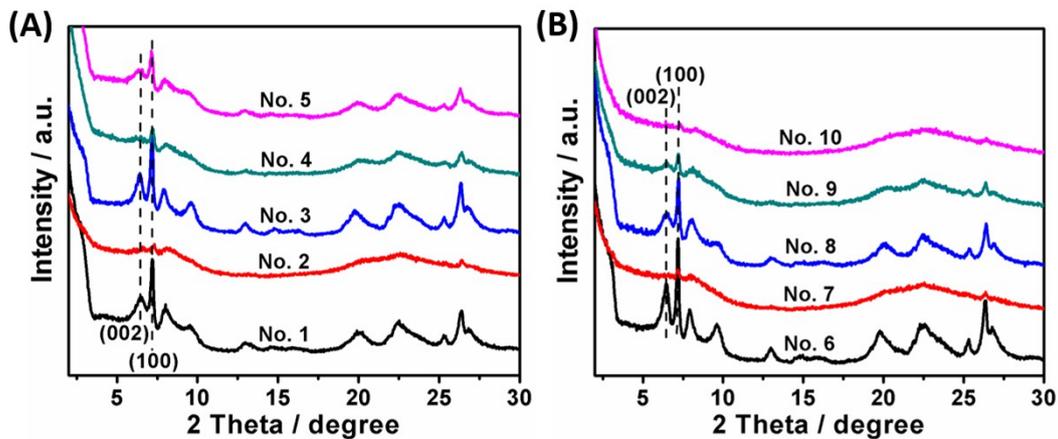
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**Table S1** Different recipes for the synthesis of precursors of thin Ti-MWW materials.

Entry	Gel composition	Hydrothermal condition	Crystallinity
No. 1	1 SiO <sub>2</sub> : 0.035 DEDMS : 0.033 TiO <sub>2</sub> : 0.67 B <sub>2</sub> O <sub>3</sub> : 1.4 PI : 30 H <sub>2</sub> O	Pre-heated at 403 K and 423 K each for 1 day, then DEDMS added, further crystallized at 443 K for 5 days	High (Dis-ordered layered precursor)
No. 2	1 SiO <sub>2</sub> : 0.035 DEDMS : 0.033 TiO <sub>2</sub> : 0.67 B <sub>2</sub> O <sub>3</sub> : 1.4 PI : 30 H <sub>2</sub> O	Pre-heated at 403 K for 1 day, then DEDMS added, further crystallized at 423 K for 1 day, then at 443 K for 5 days	Very low + Amorphous
No. 3	1 SiO <sub>2</sub> : 0.035 DEDMS : 0.033 TiO <sub>2</sub> : 0.67 B <sub>2</sub> O <sub>3</sub> : 1.4 PI : 30 H <sub>2</sub> O	Pre-heated at 403 K, 423 K and 443 K each for 1 day, then DEDMS added, further crystallized at 443 K for 4 days	Very high (Ordered layered precursor)
No. 4	1 SiO <sub>2</sub> : 0.035 DEDMS : 0.033 TiO <sub>2</sub> : 0.67 B <sub>2</sub> O <sub>3</sub> : 1.4 PI : 30 H <sub>2</sub> O	Pre-heated at 423 K for 2 days, then DEDMS added, further crystallized at 423 K for 5 days	Low + Amorphous
No. 5	1 SiO <sub>2</sub> : 0.035 DEDMS : 0.033 TiO <sub>2</sub> : 0.67 B <sub>2</sub> O <sub>3</sub> : 1.4 PI : 30 H <sub>2</sub> O	Pre-heated at 423 K for 3 days, then DEDMS added, further crystallized at 423 K for 3 days	High (Dis-ordered layered precursor)
No. 6	1 SiO <sub>2</sub> : 0.02 DEDMS : 0.033 TiO <sub>2</sub> : 0.67 B <sub>2</sub> O <sub>3</sub> : 1.4 PI : 30 H <sub>2</sub> O	Pre-heated at 403 K and 423 K each for 1 day, then DEDMS added, further crystallized at 443 K for 5 days	Very high (Ordered layered precursor)
No. 7	1 SiO <sub>2</sub> : 0.05 DEDMS : 0.033 TiO <sub>2</sub> : 0.67 B <sub>2</sub> O <sub>3</sub> : 1.4 PI : 30 H <sub>2</sub> O	Pre-heated at 403 K and 423 K each for 1 day, then DEDMS added, further crystallized at 443 K for 5 days	Very low + Amorphous
No. 8	1 SiO <sub>2</sub> : 0.035 DCDMS : 0.033 TiO <sub>2</sub> : 0.67 B <sub>2</sub> O <sub>3</sub> : 1.4 PI : 30 H <sub>2</sub> O	Pre-heated at 403 K and 423 K each for 1 day, then DEDMS added, further crystallized at 443 K for 5 days	High (Dis-ordered layered precursor)
No. 9	1 SiO <sub>2</sub> : 0.035 CDMES : 0.033 TiO <sub>2</sub> : 0.67 B <sub>2</sub> O <sub>3</sub> : 1.4 PI : 30 H <sub>2</sub> O	Pre-heated at 403 K and 423 K each for 1 day, then DEDMS added, further crystallized at 443 K for 5 days	Low + Amorphous
No. 10	1 SiO <sub>2</sub> : 0.035 CDMPMS : 0.033 TiO <sub>2</sub> : 0.67 B <sub>2</sub> O <sub>3</sub> : 1.4 PI : 30 H <sub>2</sub> O	Pre-heated at 403 K and 423 K each for 1 day, then DEDMS added, further crystallized at 443 K for 5 days	Very low + Amorphous

DEDMS: diethoxydimethylsilane; DCDMS: dichlorodimethylsilane;

CDMES: chlorodimethylethylsilane; CDMPMS: chlorodimethylphenylsilane.

**Fig. S1** Powder XRD patterns of samples synthesized with different recipes.

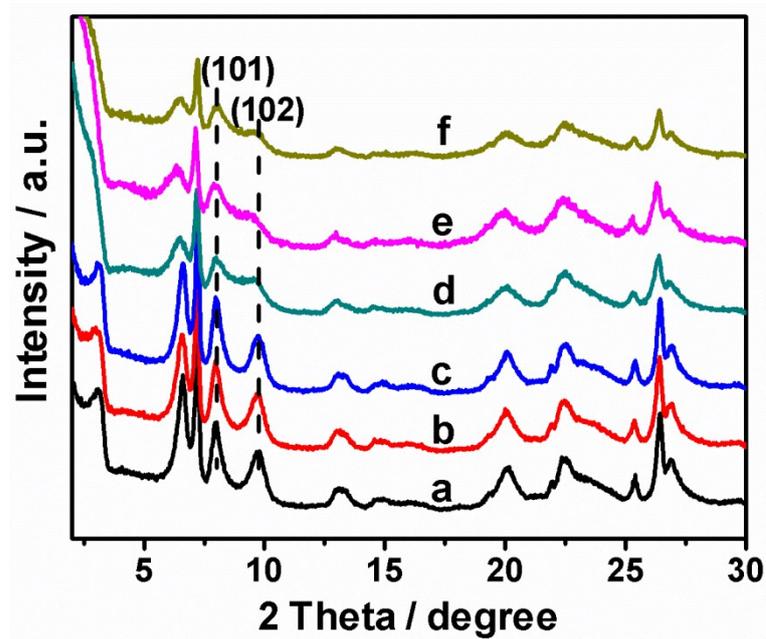


Fig. S2 Powder XRD patterns of as-synthesized Ti-MWW(50) (a), Ti-MWW(20) (b), Ti-MWW(30) (c), O-Ti-MWW(50) (d), O-Ti-MWW(20) (e) and O'-Ti-MWW(30) (f).

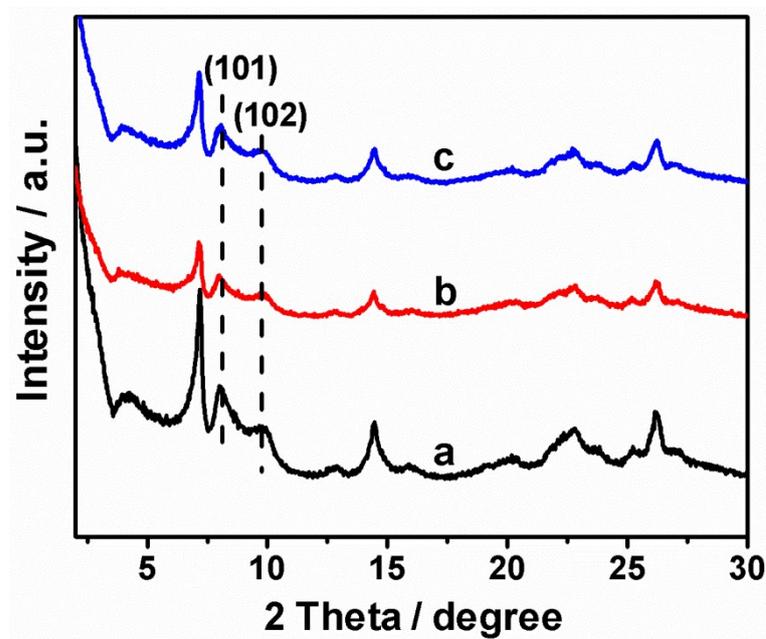
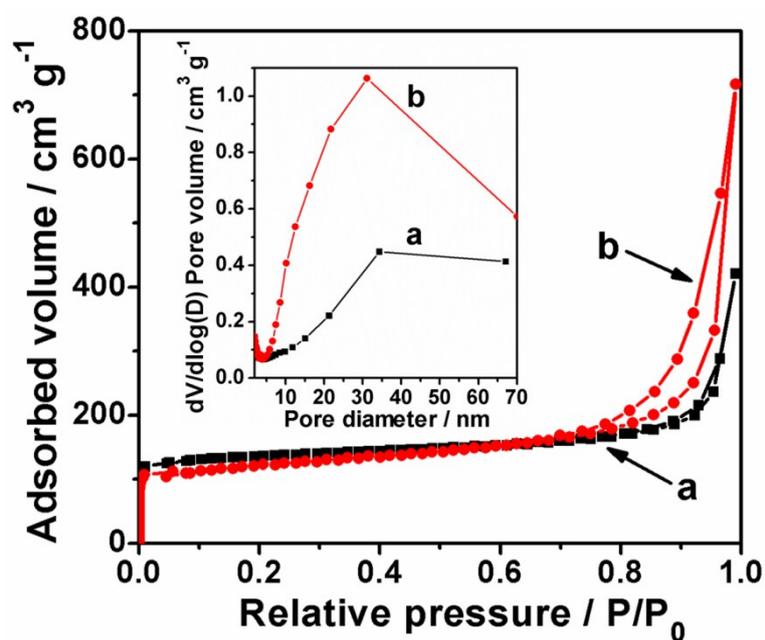


Fig. S3 Powder XRD patterns of O-Ti-MWW(50)-AT-C (a), O-Ti-MWW(20)-AT-C (b) and O'-Ti-MWW(30)-AT-C (c).

**Table S2** Physicochemical properties of Ti-MWW(50)-AT-C and O-Ti-MWW(50)-AT-C.

Sample	Specific surface area (SSA) / $\text{m}^2 \text{g}^{-1}$			Pore volume / $\text{cm}^3 \text{g}^{-1}$	
	$S_{\text{total}}$	$S_{\text{internal}}$	$S_{\text{external}}$	$V_{\text{total}}$	$V_{\text{micropore}}$
Ti-MWW(50)-AT-C	438.8	323.0	115.8	0.596	0.154
O-Ti-MWW(50)-AT-C	482.7	271.5	211.2	1.151	0.129



**Fig. S4** Nitrogen adsorption-desorption isotherms and pore size distributions (inset) of Ti-MWW(20)-AT-C (a) and O-Ti-MWW(20)-AT-C (b).

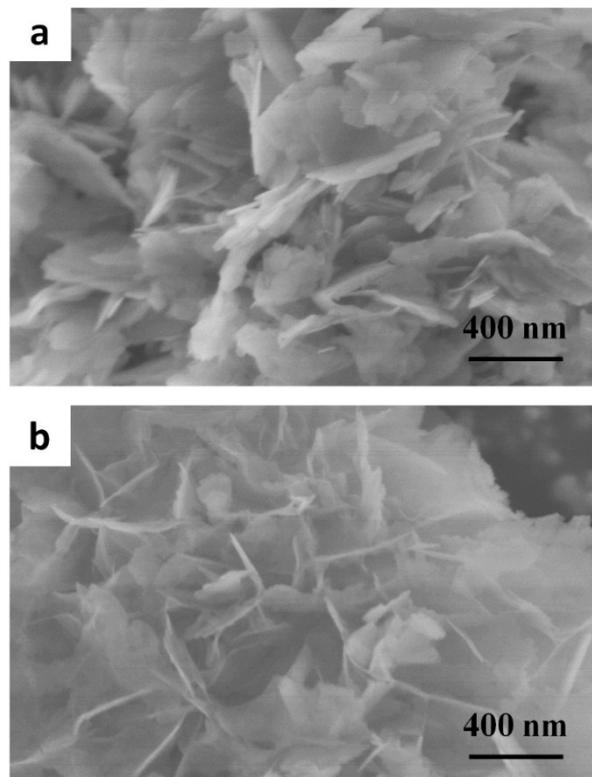


Fig. S5 SEM images of Ti-MWW(50)-AT-C (a) and O-Ti-MWW(50)-AT-C (b).

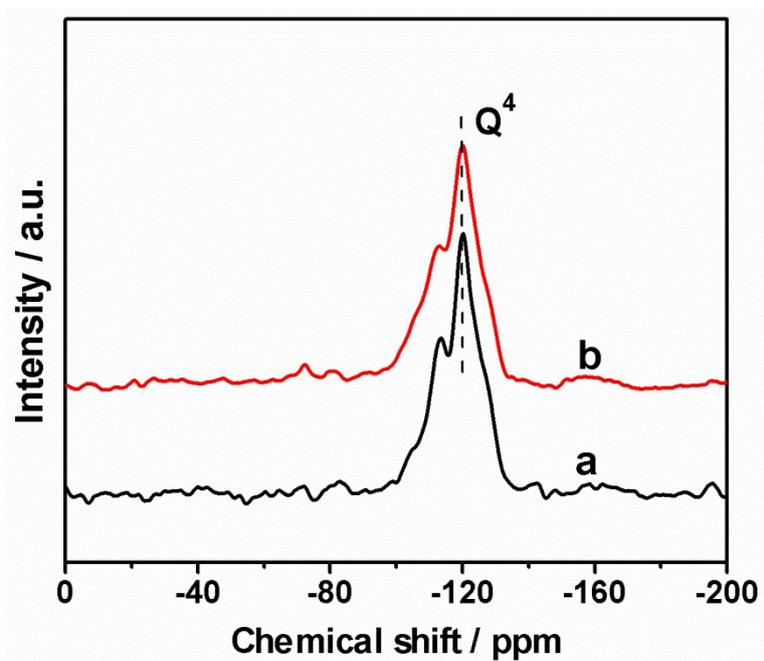


Fig. S6  $^{29}\text{Si}$  NMR spectra of BTM-7d (a) and OBTM-7d (b).

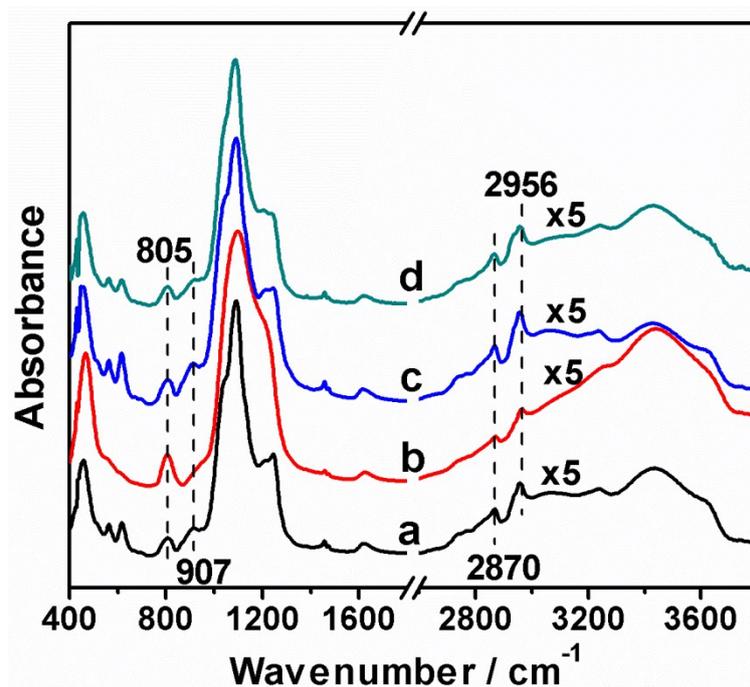


Fig. S7 IR spectra of BTM-4d (a), OBTM-4d (b), BTM-7d (c) and OBTM-7d (d).

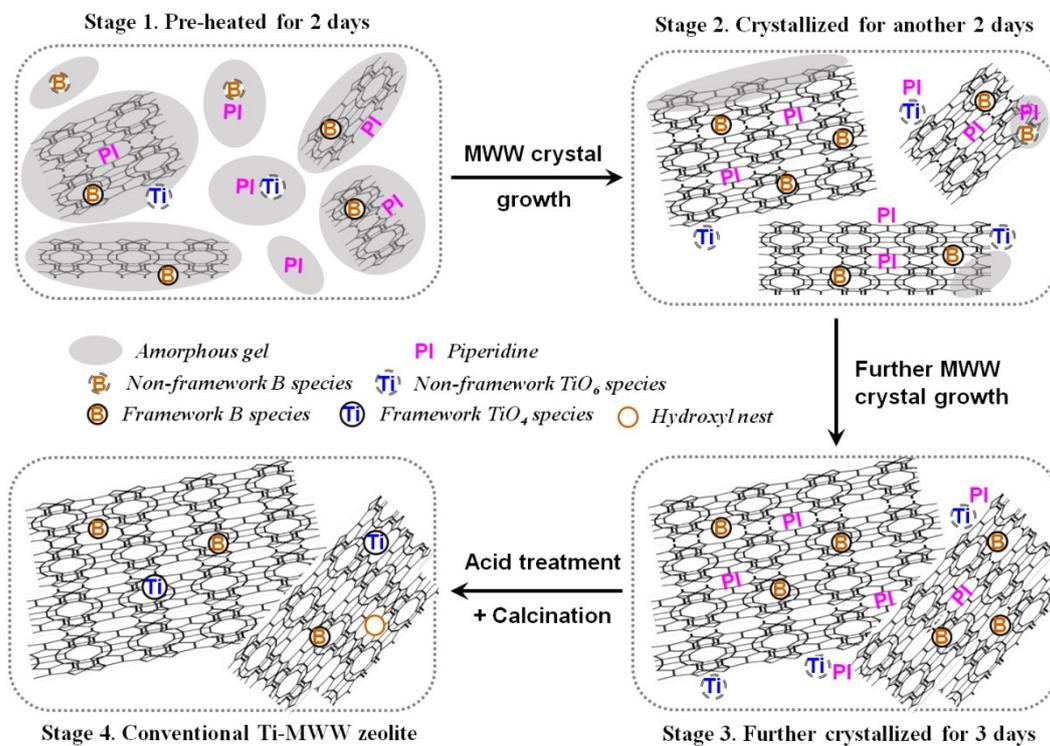


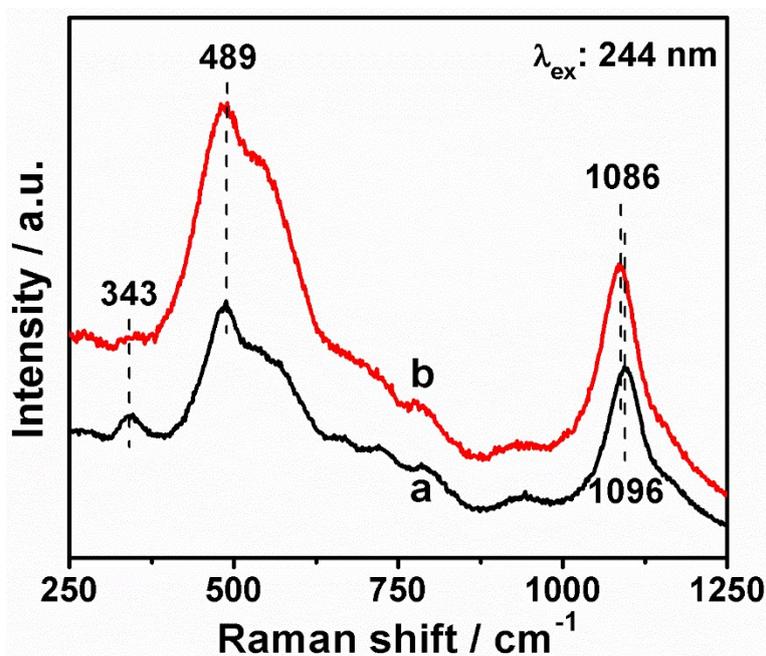
Fig. S8 A schematic diagram for possible formation mechanism of conventional Ti-MWW zeolite.

**Table S3** Catalytic performance of Ti-MWW(50)-AT-C and O-Ti-MWW(50)-AT-C for epoxidation of olefins.

Olefin	Catalyst	Si/Ti ratio	Conversion / %	Selectivity / %			TON
				Epoxide	Diol	Others	
Cyclohexene <sup>a</sup>	Ti-MWW(50)-AT-C	113.9	9.4	92	8	/	128
	O-Ti-MWW(50)-AT-C	93.6	12.4	92	8	/	139
1-Hexene <sup>b</sup>	Ti-MWW(50)-AT-C	113.9	15.8	99	1	/	216
	O-Ti-MWW(50)-AT-C	93.6	9.2	99	1	/	103

Reaction conditions: catalyst, 50 mg; olefin, 10 mmol; oxidant, 10 mmol; acetonitrile, 10 mL; temperature, 333 K; time, 2 h.

<sup>a</sup> TBHP (70 wt% in water) as the oxidant, <sup>b</sup> H<sub>2</sub>O<sub>2</sub> (30 wt%) as the oxidant.



**Fig. S9** 244 nm excited UV resonance Raman spectra of Ti-MWW(20)-AT-C (a) and O-Ti-MWW(20)-AT-C (b).